

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application No.	:	10/549,440	Confirmation No. 5587
Applicant	:	Takeo Okabe	
371 Filed	:	September 16, 2005	
Art Unit	:	1793	
Examiner	:	Sikyin Ip	
Customer No.	:	00270	
Title	:	COPPER ALLOY SPUTTERING TARGET, PROCESS FOR PRODUCING THE SAME AND SEMICONDUCTOR ELEMENT WIRING	

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

RESPONSE TO RESTRICTION REQUIREMENT

Sir:

This is a timely response to the written Restriction Requirement dated March 21, 2008.

Election

In the present application, Applicant elects without traverse to prosecute the invention directed to a sputtering target. Thus, the Group I claims are elected and include claims 1 and 16-26.

Please charge any deficiency or credit any overpayment for entering this Response to our deposit account no. 08-3040.

Respectfully submitted,
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